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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/713,269	11/17/2003	Kousuke Suzuki	108946.01	1481	
25944	7590 01/27/2005		EXAM	EXAMINER	
OLIFF & BERRIDGE, PLC P.O. BOX 19928 ALEXANDRIA, VA 22320			KIM, PE	KIM, PETER B	
			ART UNIT	PAPER NUMBER	
			2851		
			DATE MAILED: 01/27/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
Office Action Commons	10/713,269	SUZUKI, KOUSUKE			
Office Action Summary	Examiner	Art Unit			
	Peter B. Kim	2851			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address			
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be timed within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONEI	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed on	_ •				
2a) ☐ This action is FINAL . 2b) ☒ This	This action is FINAL . 2b) This action is non-final.				
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is				
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims					
4)⊠ Claim(s) <u>1-15,18,20-27,29-36 and 39</u> is/are pending in the application.					
4a) Of the above claim(s) is/are withdrawn from consideration.					
5) Claim(s) <u>1-15,18,20,23-27,29,32,33,35,36 and 39</u> is/are allowed.					
6)⊠ Claim(s) <u>21,22,31 and 34</u> is/are rejected.	Claim(s) is/are objected to.				
•					
8) Claim(s) are subject to restriction and/or	r election requirement.				
Application Papers					
9) The specification is objected to by the Examiner.					
10)⊠ The drawing(s) filed on <u>17 November 2003</u> is/are: a)⊠ accepted or b)⊡ objected to by the Examiner.					
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).					
11) The oath or declaration is objected to by the Ex	aminer. Note the attached Office	Action or form PTO-152.			
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of:					
1. ☐ Certified copies of the priority documents have been received.					
 2. Certified copies of the priority documents have been received in Application No. <u>09/787,364</u>. 3. Copies of the certified copies of the priority documents have been received in this National Stage 					
application from the International Bureau	•	a in the Haterian Stage			
* See the attached detailed Office action for a list of the certified copies not received.					
Attachment(s)					
1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413)					
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) 	Paper No(s)/Mail Da	ite atent Application (PTO-152)			
Paper No(s)/Mail Date 112003.	6) Other:				

DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.

Claims 21, 22, 30, 31, and 34 are rejected under 35 U.S.C. 102(a) as being anticipated by Shinonaga et al. (Shinonaga) (5,838,426).

Shinonaga discloses an exposure method using a projection exposure apparatus for illuminating a pattern on a mask (1) by an illumination light and projecting an image of the pattern onto a substrate (9) comprising a illumination optical system (27, 28, 29), a projection optical system (7), wavelength adjusting device (32), an image formation characteristic measurement system (col. 10, lines 43-60, detecting changes in focusing). A control system (ref. 15, 13, 17, 31, 32, 16, 22, 18, 14, 19, 20, 21), connected to the wavelength adjusting device and the image formation characteristics measurement system (Fig. 1), changing at least one condition of illumination condition by changing a wavelength of illumination light for illuminating the pattern on the first surface (1) (col. 6, lines 13-39), and detecting a change amount of image formation characteristics of an image projected on to the second surface (9) via the projection optical system (7) (col. 10, lines 43-60), detecting changes in focusing). Shinonaga discloses an installation environment measuring system for measuring and determining a change amount of the environment (22, 19, 21, 20), and changing a wavelength of the illumination light according to the change amount installation environment (col. 9, lines 25-55). Besides the first technique

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for adjusting the image formation characteristics by changing the wavelength, Shinonaga also teaches changing the image formation characteristics (change in focusing) by correcting the focus position of the wafer (col. 10, lines 48-60). Shinonaga discloses in col. 4, line 57 – col. 6, line 29, the preparation operation for projecting the image of the pattern. Shinonaga also discloses the method and the apparatus wherein the change amount of the environment is the difference between the measure and reference environment (col. 10, lines 61-67), and the change amount of the image formation characteristics is caused by change in wavelength (col. 10, lines 48-60). Shinonaga also discloses the projection optical system made of plurality of glass (col. 11, lines 64-67), and providing gas supplied inside the projection optical system and the change in environment is the change of atmospheric pressure (col. 9, lines 7-62).

Allowable Subject Matter

Claims 1-15, 18, 20, 23-27, 29, 32, 33, 35, 36, and 39 are allowed.

None of the prior art of record teaches or discloses controlling the formation characteristics measurement to system to measure a change amount of the image formation characteristics while changing the wavelength and determining a predetermined relationship between a change amount of the installation environment of the projection optical system and the change amount of the image formation characteristics based on the measurement results for the each condition.

None of the prior art of record teaches or discloses an exposure method or apparatus with a first and second image formation characteristic adjustment where the second technique is applied when the first technique could not completely make the correction or when the change amount of the change in the environment is greater than a predetermined value.

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Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Peter B. Kim whose telephone number is (571) 272-2120. The examiner can normally be reached on 8:00 AM - 5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Judy Nguyen can be reached on (571) 272-2258. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Peter B. Kim Primary Examiner

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January 21, 2005